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Commissioner for Patents, Alexandria, VA 22313-1450.

(Date of Deposit)

Karen Cinq-Mars

(Signature)

(Date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



In Re Application of : May 18, 2004

Lavin et al. :

Serial No. 10/707,778 : Examiner:

Filed: 01-12-04 : IBM Corporation
Dept. 18G/Bldg. 300-482
2070 Route 52
Hopewell Junction
New York 12533-6531

Title: SYSTEM AND METHOD OF SMOOTHING
MASK SHAPES FOR IMPROVED PLACEMENT
OF SUB-RESOLUTION ASSIST FEATURES :

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under
37 C.F.R. § 1.56 and in accordance with the practice under
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to
the documents listed on the enclosed Form PTO-1449. Copies of the
listed documents are also enclosed, excluding US patents.

It is respectfully requested that the above information be
considered by the Examiner and that a copy of the enclosed Form
PTO-1449 be returned indicating that such information has been
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030323US1

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

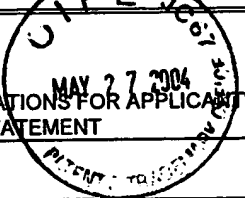
Respectfully submitted,

A handwritten signature in dark ink, appearing to read "Todd M. C. Li", is written over a horizontal line.

Todd M. C. Li
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FORM PTO-1449 (Modified)		ATTY. DOCKET NO. FIS920030323US1	SERIAL NO. 10/707,778
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT		APPLICANT: LAVIN ET AL.	
(Use several sheets if necessary)		FILING DATE: 01-12-04	GROUP: 1756

REFERENCE DESIGNATION OTHER ART

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

EXAMINER INITIALS		
AJ		Granik et al., "Two-dimensional G-MEEF Theory and Applications," Proceedings of SPIE - The International Society for Optical Engineering v.4754 2002 p.146-155.
AI		LaCour et al., "Model-Based OPC For Sub-Resolution Assist Feature Enhanced Layouts," Proceedings of SPIE - The International Society for Optical Engineering, 2002.
AK		Joesten et al., "The Effect Of Scattering Bar Assist Features In 193 Nm Lithography," Optical Microlithography XV. Proceedings of SPIE - The International Society for Optical Engineering v.4691 II 2002 p.861-870.
AL		Shi et al., "Understanding The Forbidden Pitch Phenomenon And Assist Feature Placement," Metrology, Inspection, and Process Control for Microlithography XVI. Proceedings of SPIE - The International Society for Optical Engineering v.4689 II 2002 p.985-996.
AM		Reblinky et al., "Lithographic Comparison Of Assist Feature Design Strategies," Optical Microlithography XV Santa Clara, CA, USA 5-8 March 2002.
AN		Smith, "Mutually Optimizing Resolution Enhancement Techniques: Illumination, APSM, Assist Feature OPC, And Gray Bars," Optical Microlithography XIV. Proceedings of SPIE - The International Society for Optical Engineering v.4346 n.1 2001 p.471-485.
AO		Liebman et al., "Optimizing Style Options For Sub-Resolution Assist Features" Optical Microlithography XIV. Proceedings of SPIE - The International Society for Optical Engineering v.4346 n.1 2001 p.141-152.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

